

Title (en)

METHOD FOR ETCHING A PATTERN ON A COATING DEPOSITED ON A SUBSTRATE; CORRESPONDING SUBSTRATE

Title (de)

VERFAHREN ZUM ÄTZEN EINES MUSTERS AUF EINER AUF EINEM SUBSTRAT ABGESCHIEDENEN BESCHICHTUNG; ENTSPRECHENDES SUBSTRAT

Title (fr)

PROCÉDÉ DE GRAVURE D'UN MOTIF SUR UN REVÊTEMENT DÉPOSÉ SUR UN SUBSTRAT; SUBSTRAT CORRESPONDANT

Publication

EP 4076826 A1 20221026 (FR)

Application

EP 20848862 A 20201218

Priority

- FR 1915197 A 20191220
- FR 2020052569 W 20201218

Abstract (en)

[origin: WO2021123690A1] The present invention relates to a method for processing a coating on a substrate passing through a processing unit generating a laser beam, said method consisting in producing a pattern having a plurality of lines or portions extending in the direction of travel and/or the direction orthogonal to the direction of travel, said pattern being repeated to cover and process the surface of the substrate.

IPC 8 full level

B23K 26/00 (2014.01); **B23K 26/08** (2014.01); **B23K 26/082** (2014.01); **B23K 26/352** (2014.01); **B23K 26/362** (2014.01); **B23K 26/402** (2014.01); **C03C 17/00** (2006.01); **B23K 101/34** (2006.01); **B23K 103/00** (2006.01)

CPC (source: EP US)

B23K 26/0006 (2013.01 - EP); **B23K 26/082** (2015.10 - EP); **B23K 26/0846** (2013.01 - EP US); **B23K 26/355** (2018.07 - EP US); **B23K 26/362** (2013.01 - EP US); **B23K 26/402** (2013.01 - EP); **C03C 17/40** (2013.01 - EP); **B23K 2101/34** (2018.07 - EP US); **B23K 2103/42** (2018.07 - EP); **B23K 2103/54** (2018.07 - EP); **C03C 2218/328** (2013.01 - EP)

Citation (search report)

See references of WO 2021123690A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

Designated extension state (EPC)

BA ME

Designated validation state (EPC)

KH MA MD TN

DOCDB simple family (publication)

FR 3105045 A1 20210625; **FR 3105045 B1 20220812**; EP 4076826 A1 20221026; US 2023045271 A1 20230209; WO 2021123690 A1 20210624

DOCDB simple family (application)

FR 1915197 A 20191220; EP 20848862 A 20201218; FR 2020052569 W 20201218; US 202017787081 A 20201218